



## SMALL-SCALE INSTALLATION FOR THERMAL PROCESSING OF PLATES AND MATERIALS IN VACUUM OR GAS ENVIRONMENT

# OTJIG TM-5

### Purpose:

Automatic thermal processing of plates and materials (annealing, drying, diffusant rectification, reconstruction of crystal structures) at standard pressure in oxidative or neutral environment.

### Special characteristics:

- Group processing of 30 substrates up to  $\varnothing$  100 mm;
- Quartz reactor with sealed working area;
- Working temperature range 200 – 500 °C;
- Working gases –  $\text{PH}_3$ ,  $\text{N}_2\text{O}$ ,  $\text{O}_2$ ,  $\text{NH}_3$ ,  $\text{SiH}_4$ ,  $\text{N}_2$  ;
- Microprocessing control system;
- Consumed power not more than 7 kW;
- The ability to embed into clean room;
- 3 m<sup>2</sup> area per one plant.

